

at least one spot formation device to form at least one spot of radiation from at least a portion of said projection beam in said apparatus; and

at least one radiation sensor, to measure a spatial variation in intensity of defocused radiation from the at least one spot or an image thereof.

25. (Amended) A device manufactured according to the method of claim 24.

*See the attached Appendix for the changes made to effect the above claim(s).*

IN THE ABSTRACT OF THE DISCLOSURE:

Please delete the present Abstract of the Disclosure and replace it with the following new Abstract of the Disclosure.

*W* -- A method of operating a lithographic projection apparatus including forming a spot of radiation at the wafer level using a pinhole at reticle level. A sensor is defocused with respect to the spot such that it is spaced apart from the wafer level. The sensor is scanned beneath the spot to measure the angular intensity distribution of radiation at the spot and to determine the intensity distribution at the pupil plane of the projection lens system. --

*See the attached Appendix for the changes made to effect the above Abstract.*